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PB Chou, AR Rao, MC Sturzenbecker, FY Wu, ... - Machine Vision and ..., 1997 - Springer
... Patterned **wafer** inspection tools can optically detect **defects** less than 0.5 micron in di-ameter. ... Much of the excitement of ADC arises from the challenge of the classification technology ... be constructed by representing their knowledge in terms of **rules** that relate **defect** attributes to ... Cited by 43 - Related articles - St. Direct - All 3 versions Model-based clustering for integrated circuit yield enhancement JY Hwang, W Kuo - European Journal of Operational Research, 2007 - Elsevier ... The curvilinear feature is one of the typical patterns observed on wafer defect maps with ... Approximate modeling of curvilinear defect patterns with the bivariate normal distribution may ... information about the characteristics of clusters and decrease the classification capability [14]. ... Cited by 11 - Related articles - All 7 versions Monitoring wafer map data from integrated circuit fabrication processes for spatially clustered defects MH Hansen, VN Nair, DJ Friedman - Technometrics, 1997 - JSTOR ... In general, clusters of defects can be classified as either particle or process related, with particle-related clus- ters being assignable to individual machines and process- related clusters being ... MONITORING WAFER MAP DATA FOR SPATIALLY CLUSTERED DEFECTS ... Cited by 35 - Related articles - Bt. Direct - All 6 versions mya-org.jp (PDF) [PDF] Recent progress in industrial machine vision O Montadi, JLO Sanz - International Journal of Robotics and Automation, 1993 - mva-org.jp ... patches. The **likelihood** of the presence of the match of a fea- ture point in the other image should be high. It ... circuited region. To obtain statistical information on the wafer, a defect classification circuit can be used. This circuit ... Cited by 10 - Related articles - View as HTML - BL Direct - All 4 versions [PDF] Determining composition of grain mixtures by texture classification based on feature psu.edu (PDF) distributions T Olala, M Pietikäinen, J Nisula - International Journal of Pattern ..., 1996 - Citeseer ... The proposed applications include, for example, the detection and identification of surface defects on metal surfaces, textiles or semiconductor wafers, the assessment of ... This procedure was repeated for all samples and the classification error rate was determined as the ... Cited by 13 - Related articles - View as HTML - Bt. Direct - Atl 10 versions A cost-based heuristic for statistically determining sampling frequency in a wafer fab CF Chien, SC Hsu, S Peng, CH Wu - 2000 - 140.114.72.28 ... However, 100% inspection is practiced at **wafer** sort to **classify** dice, we assume that there is ... as well as the optimal allocation of inspection capacity depends on the **defect** variability ... needed for extending the proposed method to deal with the whole in-line wafer sampling strategy ... Cited by 4 - Related articles - View as HTML - All 2 versions A model-based clustering approach to the recognition of the spatial defect patterns produced during semiconductor fabrication T Yuan, W Kuo - IIE Transactions, 2008 - informaworld.com ... The indexing values for classification, the  $\gamma$  in the classification **likelihood** function (2), satisfy  $\gamma$  is  $\gamma$  if  $\gamma$  in the simulation studies, the diameter of the **wafers** is 20 cm. ... The intensity function used in the global defect generation is quadratic, that is ... Cited by 1 - Related articles - Bt. Direct - All 3 versions A hybrid fuzzy-statistical clustering approach for estimating the time of changes in fixed and variable sampling control charts A Alaeddini, M Ghazanfari, MA Nayeri - Information Sciences, 2003 - Eisevier .. and more rational than revised C-charts which are used in monitoring wafer defects during IC ... [4] use expert technology to select unstable slicing machines to control wafer slicing quality ... (2) Similar to clustering methods, change-point models are used to classify patterns: almost ... Oited by 3 - Related articles - All 2 versions Spatial defect pattern recognition on semiconductor waters using model-based clustering and Bayesian inference T Yuan, W Kuo - European Journal of Operational Research, 2008 - Elsevier Section 2 describes the mixture model used to describe the defect distributions on the  $\textbf{wafers.} \dots$ In both approaches, the locations s i are regarded as incomplete data and the complete data

are considered to be (s i , z i ), where the classification variables z i =(z i0 ,z i1 ,...,z iG ),i ...

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